

Matthew Beasley (CU-Boulder),

# OPTICAL SYSTEMS FOR THE UV

# OUTLINE

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- ✖ Bandpasses and technology
- ✖ Consequences to optical designs
- ✖ Where are the improvements in each bandpass

# UV (NOT AVAILABLE FROM GROUND)

- ✗  $<550 \text{ \AA}$  requires either grazing incidence or multilayers over small bandpass
- ✗ EUV:  $550 - 900 \text{ \AA}$
- ✗ DUV:  $900 - 1150 \text{ \AA}$
- ✗ FUV:  $1150 - 2000 \text{ \AA}$
- ✗ NUV:  $2000 - 3200 \text{ \AA}$



# EUV 550 – 900 Å

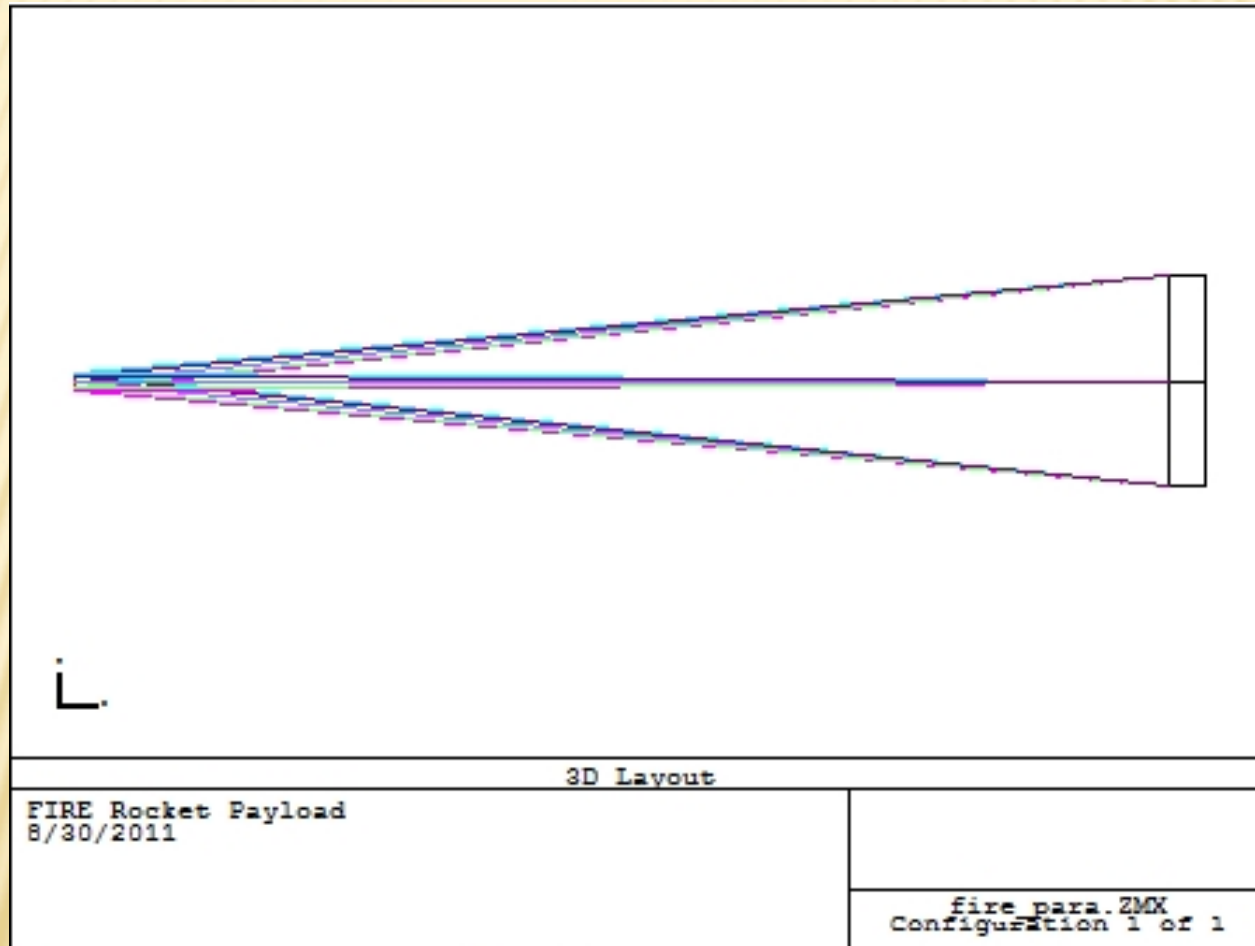
- ✖ EUV currently restricted to in-situ planetary measurements
  - + Only a few astrophysical targets in this bandpass
- ✖ Architecture completely determined by low reflectivity ( $\sim 30\%$  broadband SiC, B<sub>4</sub>C)
- ✖ Missions in this bandpass typically look at bright targets (can be small)
- ✖ Thin film metal films are only transmitting materials



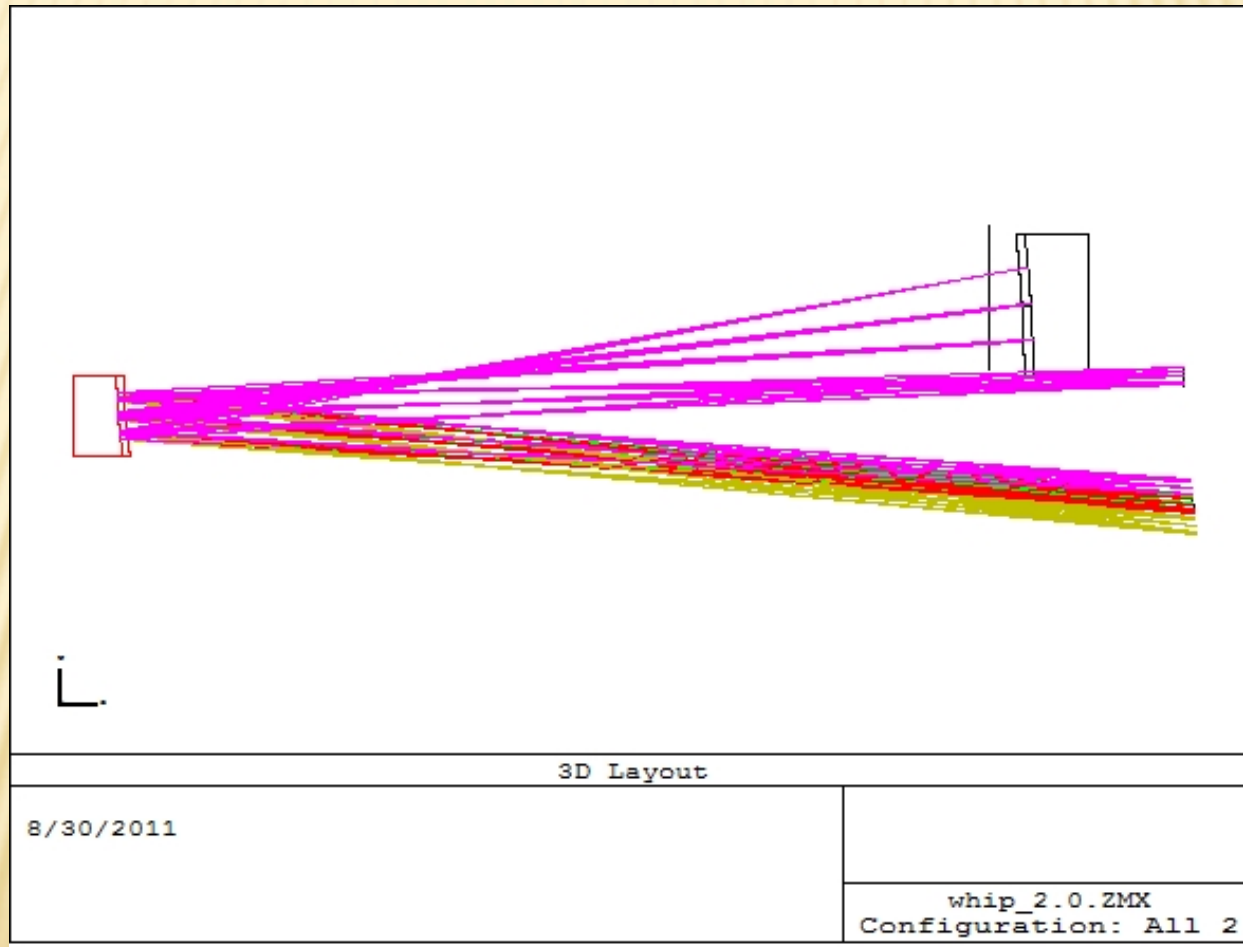
## DUV 900 – 1150 Å

- ✗ 900 – 1000 Å throughput requires SiC or B<sub>4</sub>C (30% reflectivity)
- ✗ 1000 – 1150 Å can use LiF/Al for 60% (with good efficiency through optical wavelengths)
- ✗ Architecture determined by poor reflectivity
- ✗ Thin film metals are only transmitting materials, no lenses

# INSTRUMENT FOR DUV (900 – 1000 Å)



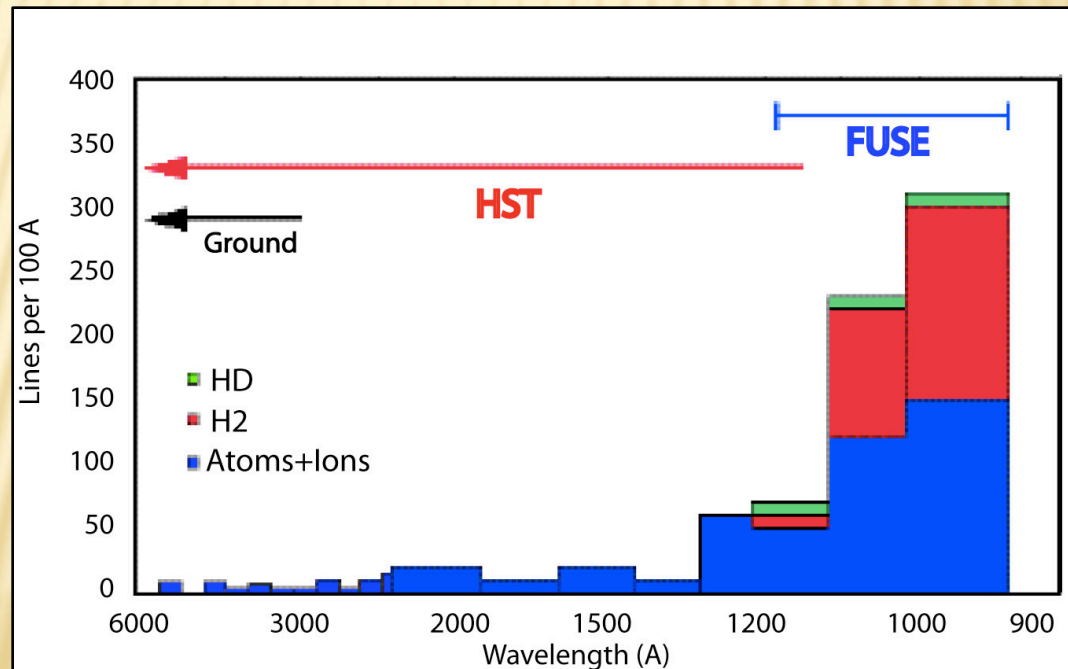
# DUV INSTRUMENT (1035 Å)





# WHY DUV? WHY WORK SO HARD?

- ✗ # of ground state transitions as function of wavelength



## FUV 1150 – 2000 Å

- ✖ MgF<sub>2</sub>/Al best choice for broadband operation
- ✖ 80% reflection allows three optic systems
- ✖ Transmitting optics (i.e., lenses) work, albeit poorly
- ✖ Good filters would be highly desirable scientifically

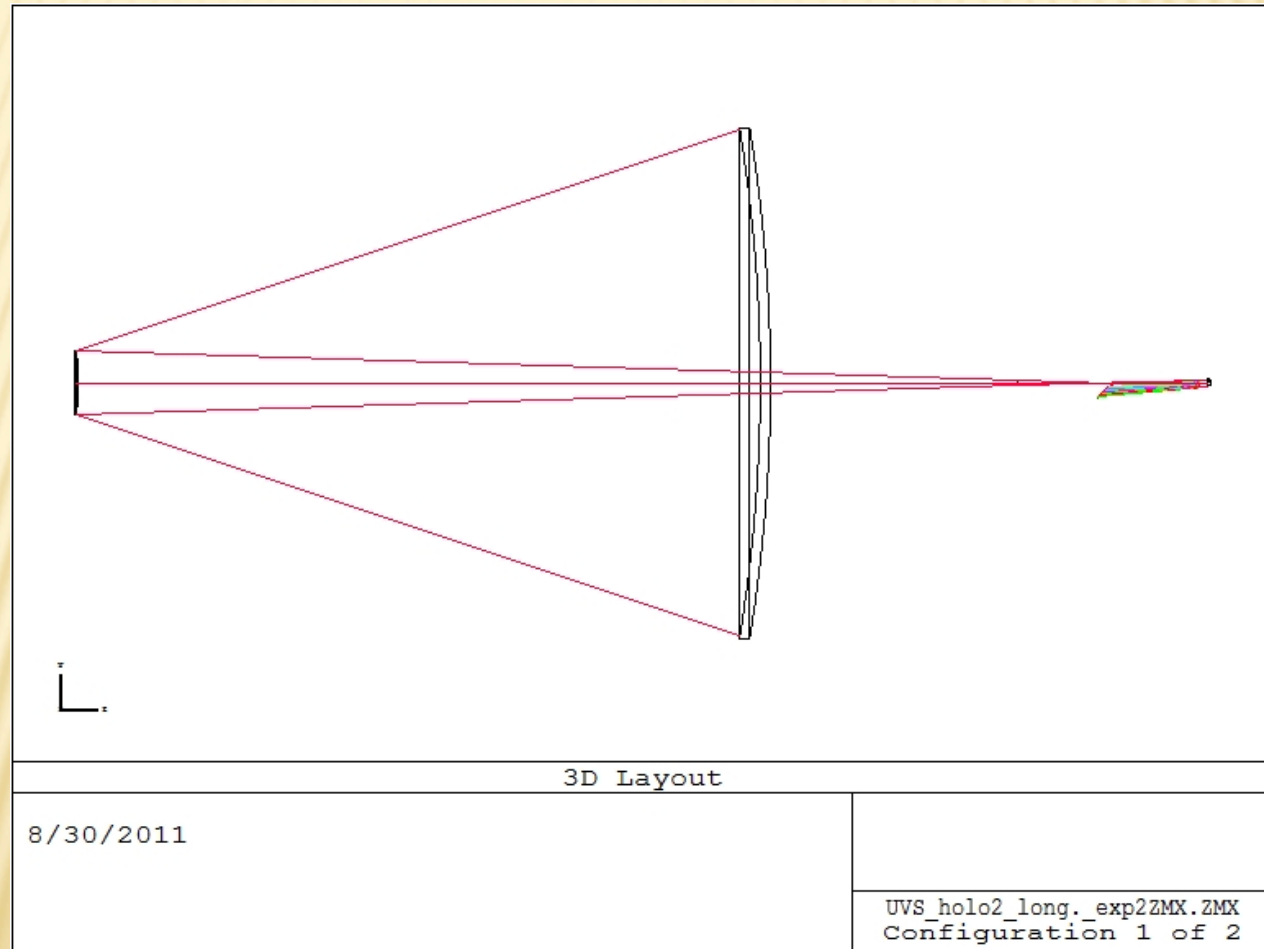


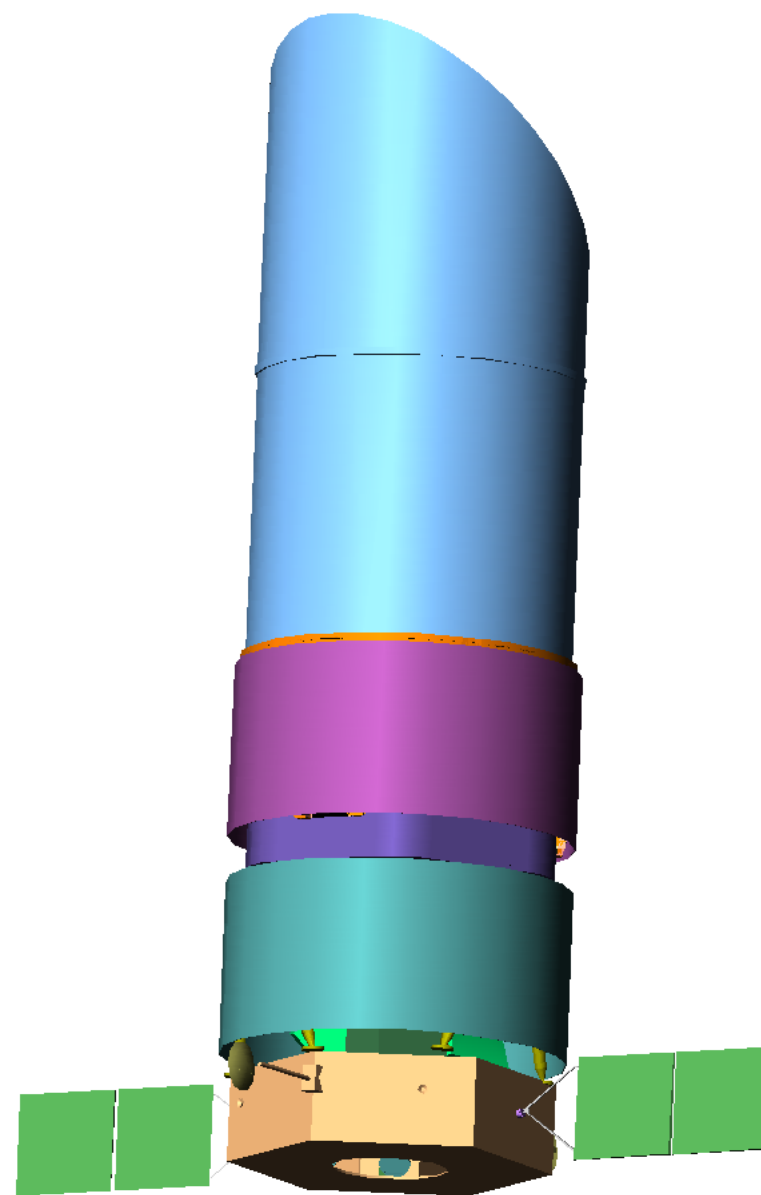
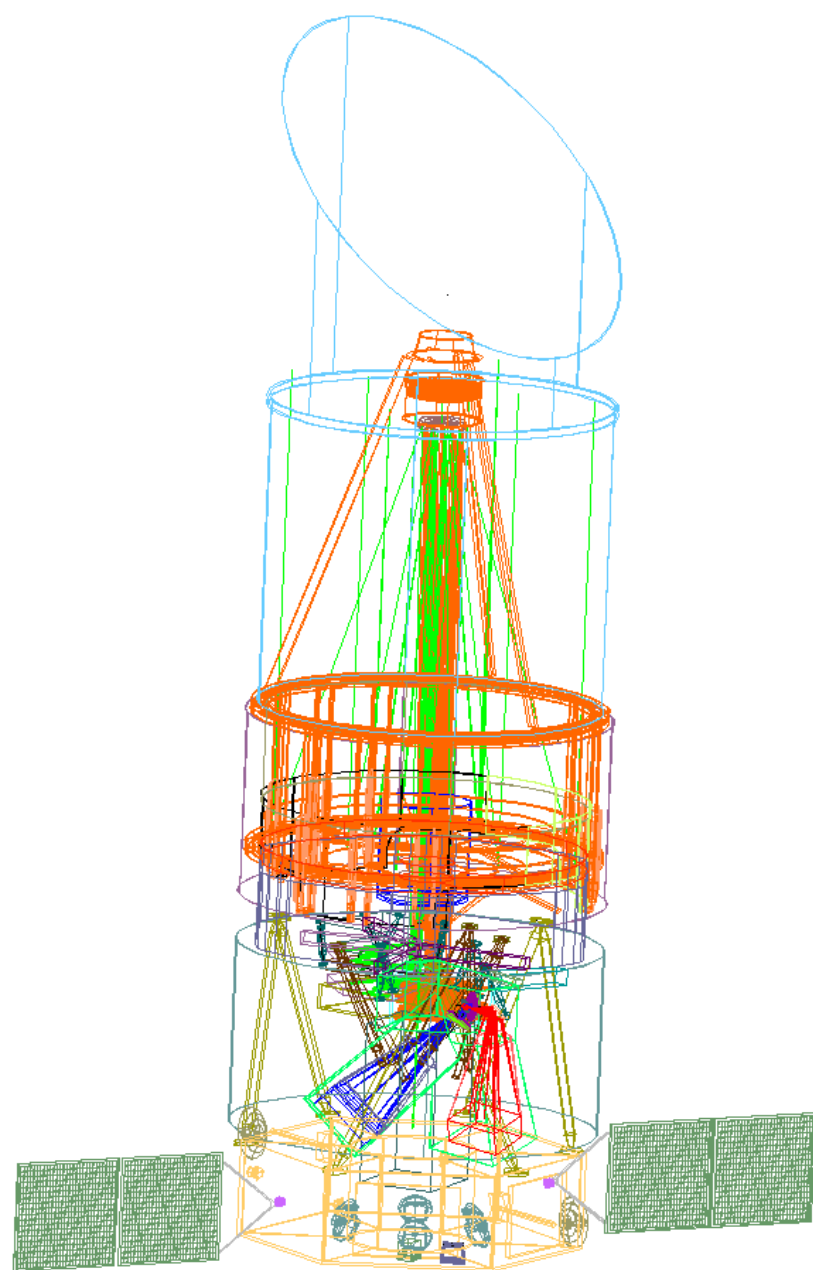
# HUBBLE FUV





# FUV INSTRUMENTS (1000 – 1600 Å)



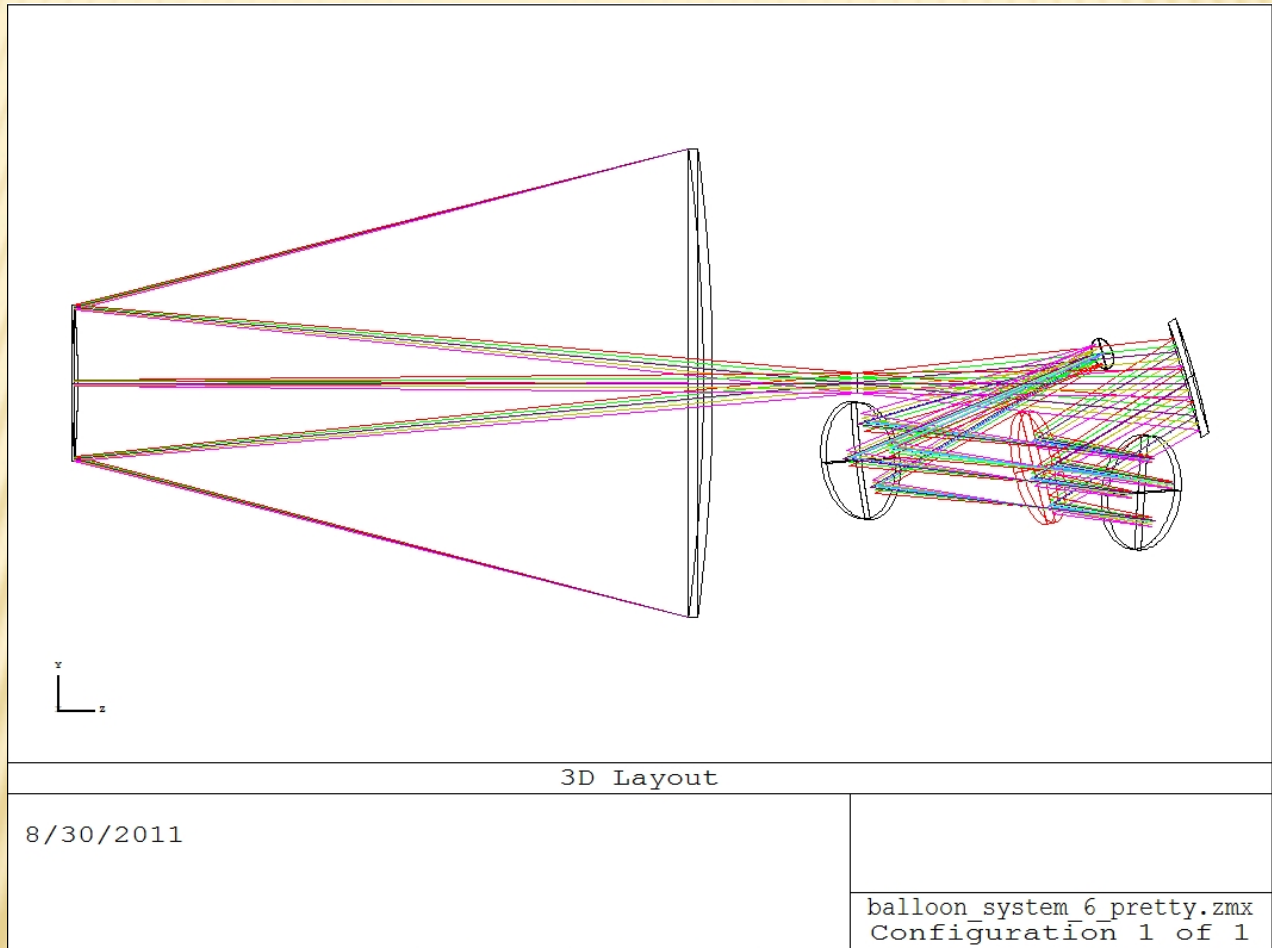


## NUV 2000 – 3200 Å

- ✖ Excellent efficiency >85% from high quality  $\text{MgF}_2$ , mirror coatings not driver for architecture
- ✖ Good optical quality, decreasing scatter issues, low airglow
- ✖ Detectors have room for improvement
- ✖ Conventional filters leave something to be desired, but work



# NUV INSTRUMENT



# BROADBAND COATINGS

- ✗ Bare metal has been used (iridium, osmium), but low ( $\sim 15\%$ ) reflectivity compromises performance
- ✗ Evaporated  $\text{MgF}_2/\text{Al}$ ,  $\text{LiF}/\text{Al}$ ,  $\text{SiC}$ ,  $\text{B}_4\text{C}$ .
  - + Represent advancements over bare high-Z metals in the UV (30 – 60%)

# CURRENT COATINGS

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- ✗ However, the  $\text{MgF}_2/\text{Al}$  and  $\text{LiF}/\text{Al}$  are simply to protect the native aluminum reflectivity and suffer short wave cutoff due to the crystal becoming opaque.
- ✗ Improvements on the way



# OPTICAL FABRICATION ISSUES

- ✘ Diffraction limit costly to achieve with NUV/FUV optics due to testing issues
- ✘ Holographic diffraction gratings limited in figure quality, typically have little impact on systems

# SCATTER

- ✗ Highly polished glass ( $< 10 \text{ \AA}$  rms) excellent
  - + New metal optics acceptable in DUV (nickel clad aluminum)
- ✗ Gratings
  - + Holographic in photoresist
    - ✗ VERY LOW ( $< 5 \times 10^{-7}$ )
  - + Holographic Ion Etched
    - ✗ Low ( $< 1 \times 10^{-5}$ )
  - + Ruled (via diamond)
    - ✗ Can be high
  - + Exotics
    - ✗ Silicon Lithography – probably low
    - ✗ Photonic material – low, may have other effects

# FILTERS (AND DICHROICS)

- ✗ EUV – thin film metal filters and multi-layer reflective systems provide modest filter capacity
- ✗ DUV – thin film filters have been used. Nothing approaching narrowband ( $R \sim 10$  is the best I'm aware of)
- ✗ FUV – conventional filters becoming available, but throughput is low and resolution is modest (compared to optical wavelengths), reflection filters better
- ✗ NUV – Selections of materials is improving, better filters, reflective filters still competitive



# DETECTORS

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- ✖ EUV – detectors (silicon/MCP based) work well, DQE is high (>60% dropping as wavelengths get long, especially for silicon)
- ✖ DUV – MCPs (or other photocathode based) have good DQE (~50%), Silicon ~30%
- ✖ FUV – MCPs (or other photocathode) best at short wavelengths, Silicon potentially better at long wavelengths
- ✖ NUV – silicon devices currently best, MCPs with GaN may be competitive

# CONTAMINATION CONTROL

- ✖ Increasingly strict the shorter the wavelength due to hydrocarbon absorption of light
- ✖ Can be a cost driver for LiF/Al optics
  - + Will result in cost increases over the entire mission for any UV instrument

# AIRGLOW

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- ✖ EUV, DUV, FUV – bright geocoronal airglow force some sort of control into instrument design
  - + In situ planetary missions consider the airglow “science”
- ✖ NUV – airglow not a significant issue

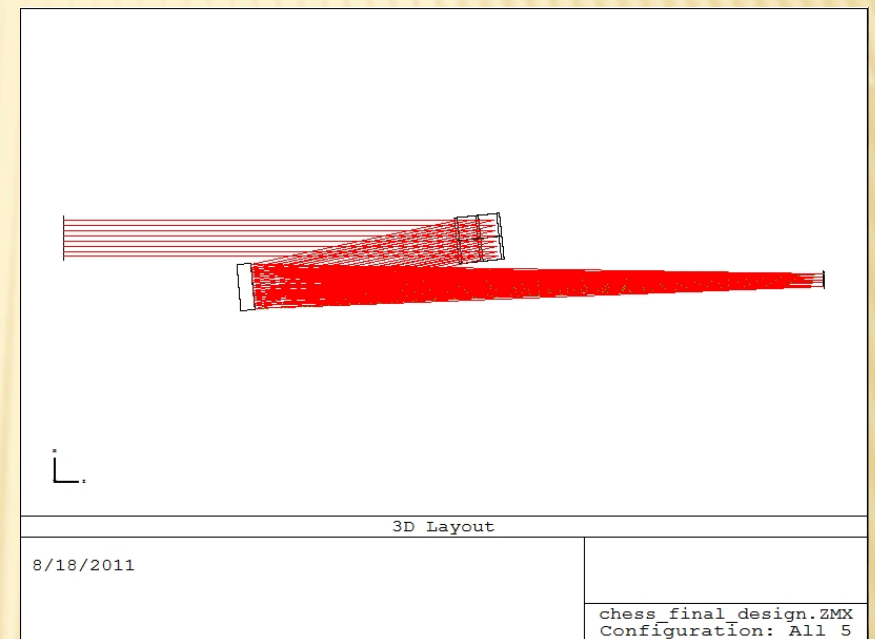
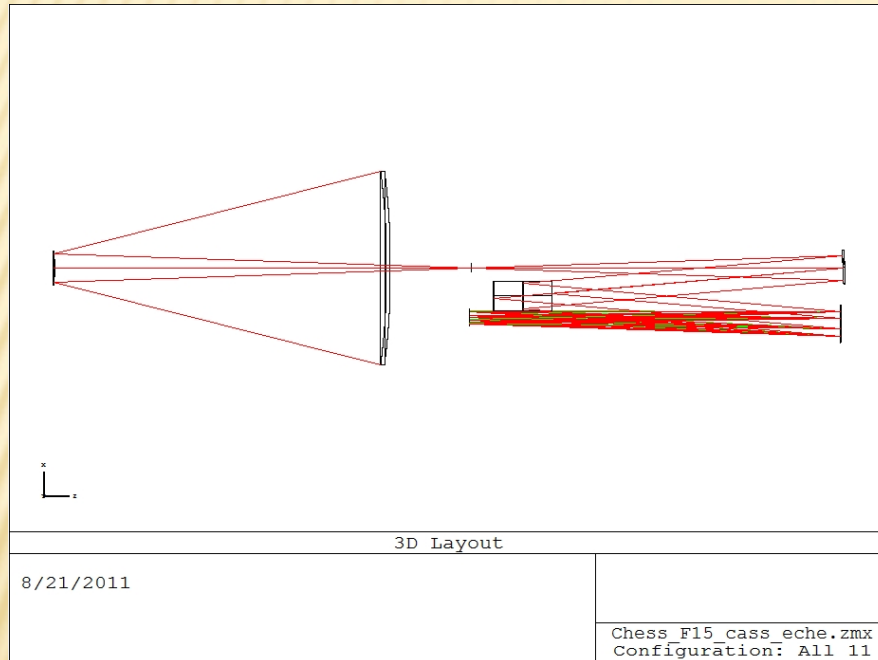


# IMPROVEMENT

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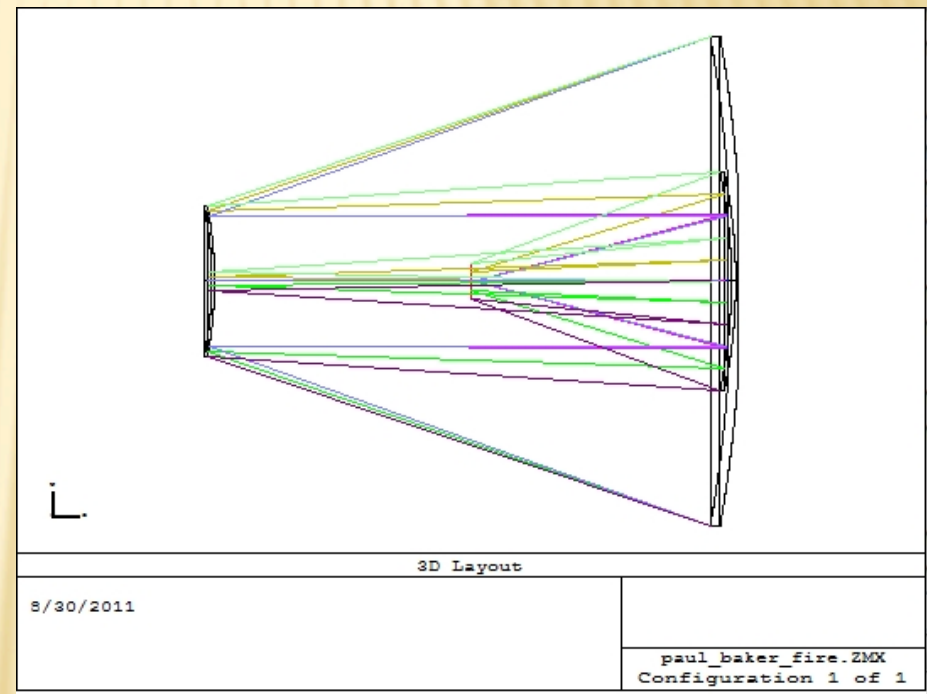
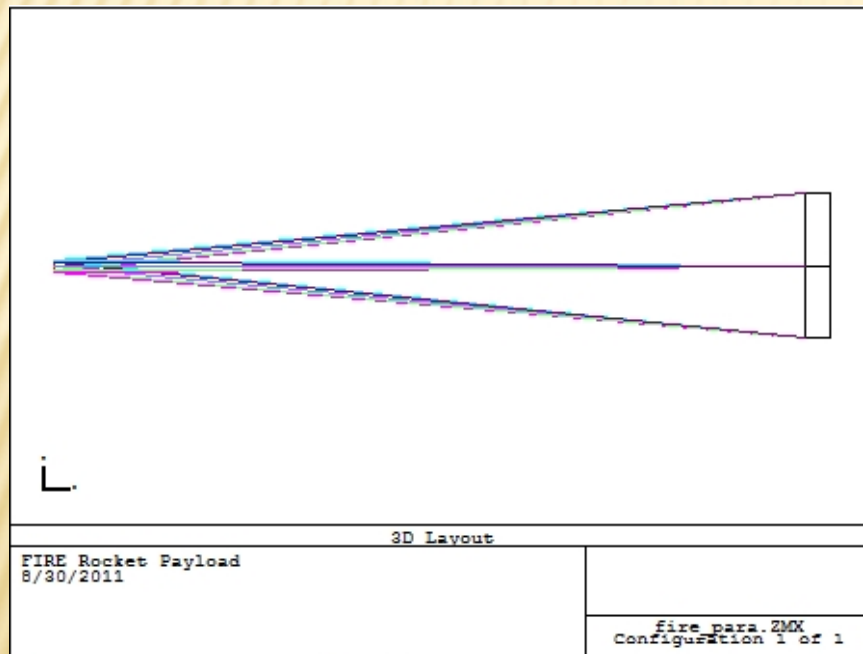
- ✖ DUV has substantial (and more profound increases in capability) available at low cost with a straightforward development path
- ✖ Other UV bands have improvement paths
  - + Detectors are being worked on (several groups here)
  - + Filters, etc

# CHESS ROCKET PAYLOAD (DUV/FUV)



These echelle systems are roughly equivalent (resolution, bandpass). The design on the left is a BETTER design.

# DUV SYSTEMS





# UPGRADE PRIORITIES

## ✕ EUV/DUV

1. Reflective coatings
2. Gratings
3. Detectors

## ✕ FUV

1. Gratings/  
Filters
2. Detectors
3. Reflective  
Coatings

## ✕ NUV

1. Detectors
2. Gratings/  
Filters
3. Reflective  
Coatings

# ASTROPHYSICAL MISSION CONCEPTS

- ✖ Three-mirror anastigmat architecture good candidate for UVOIR instrument
- ✖ Unless operations below 1150 Å required, three mirrors not a significant impact for FUV
- ✖ DUV systems would require more exotic designs to integrate UV/Optical (and performance compromises)
- ✖ UV-only mission could make these trades